

ABSTRACT

An (inner) second planarization film which is an insulating film in the form of a frame and an (outer) second planarization film which has a high profile and pillar shape are formed so as to cover the periphery of a pixel electrode. Subsequently, when an organic emissive layer is subjected to mask evaporation, only a region wherein the (outer) second planarization film is provided comes into contact with the mask. Accordingly, the occurrence of scraping of the mask or dislodging of dust can be reduced, and any resulting scrapings or dust are trapped between the (outer) second planarization film and the (inner) second planarization film.